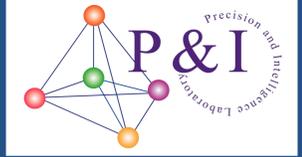


# Effect of Annealing on Mechanical Properties of Nickel Film Electrodeposited Using Supercritical CO<sub>2</sub> Emulsion Evaluated by Micro-Compression Test



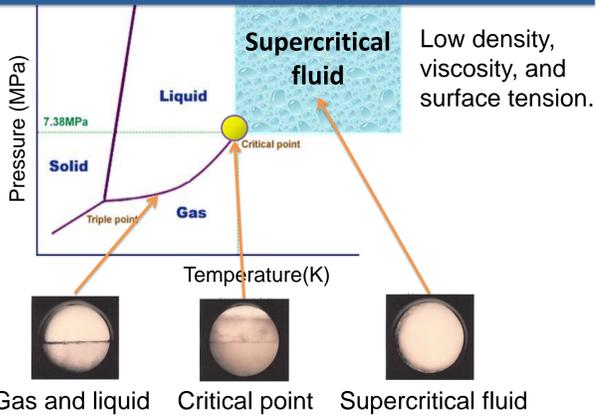
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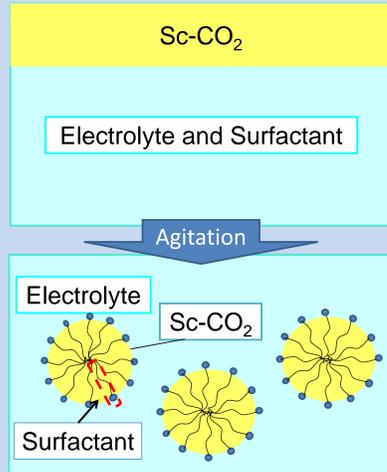
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## INTRODUCTION

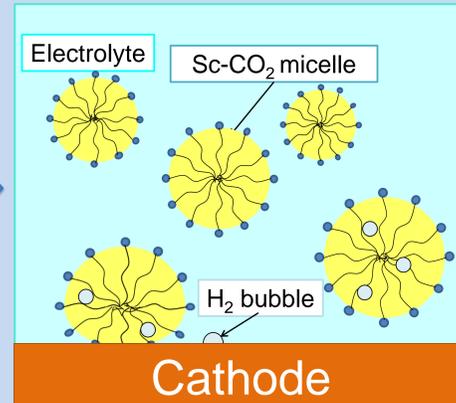
### Supercritical Carbon Dioxide (Sc-CO<sub>2</sub>)



Use supercritical CO<sub>2</sub> for electroplating



### Electroplating With Sc-CO<sub>2</sub> Emulsion (ESCE)



- ✓ Increased desorption of H<sub>2</sub> bubble from cathode
  - Void and defect free
  - ✓ Periodic on/off at the surface of the cathode
  - Grain refinement
  - Improved strength
- Possible application for MEMS components.

## EXPERIMENTAL PROCEDURE

### Electroplating With Sc-CO<sub>2</sub>

Materials	
Substrate	
➢ Cathode:	Cu substrates
➢ Anode:	Ni substrates
Additive Free Watts Bath	
➢ NiSO <sub>4</sub> ·6H <sub>2</sub> O	(300 g/l)
➢ NiCl <sub>2</sub> ·6H <sub>2</sub> O	(50 g/l)
➢ H <sub>3</sub> BO <sub>3</sub>	(50 g/l)
Surfactant	
➢ polyoxyethylene lauryl ether	(C <sub>12</sub> H <sub>25</sub> (OCH <sub>2</sub> CH <sub>2</sub> ) <sub>15</sub> OH)

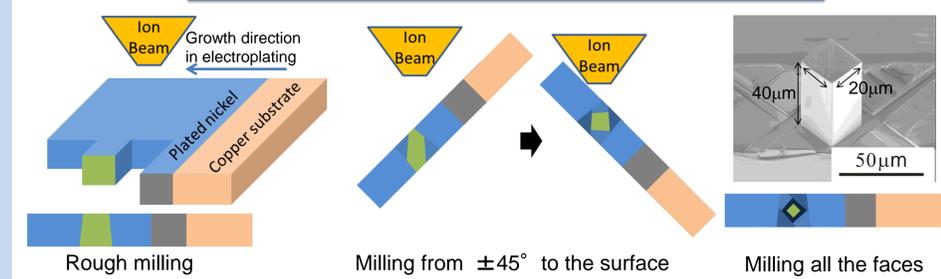
Plating conditions	
Temperature	323 K
CO <sub>2</sub> vol%	20 vol%
Current density	2 A/dm <sup>2</sup>
Pressure	15MPa

### Annealing of plated nickel

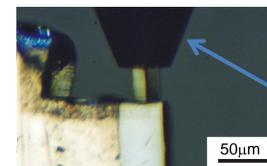
In vacuum for 2 hours  
at 150, 200, 300, 400°C

- Structural characterization
- Transmission electron backscattered diffraction (t-EBSD)
  - SEM-STEM
- Mechanical characterization
- Micro-compression test

### Fabrication of Compression Pillar by FIB



### Micro-Compression Test

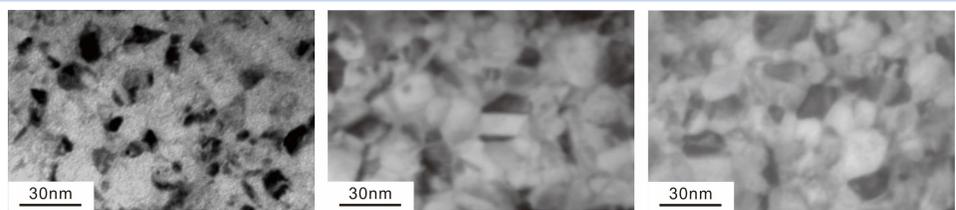


Control	Displacement rate	Load resolution
Displacement control	0.1 [µm/s]	10 [mN]

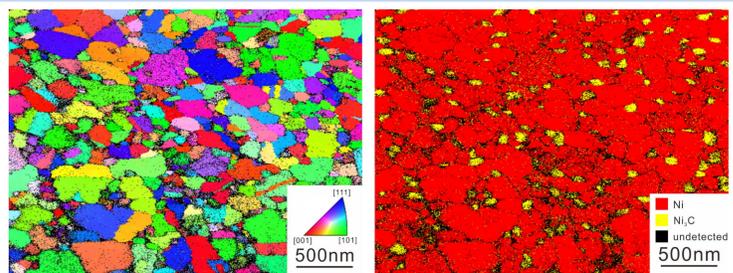
## RESULTS & DISCUSSION

### Effect of Annealing

As deposited      150°C annealed      200°C annealed



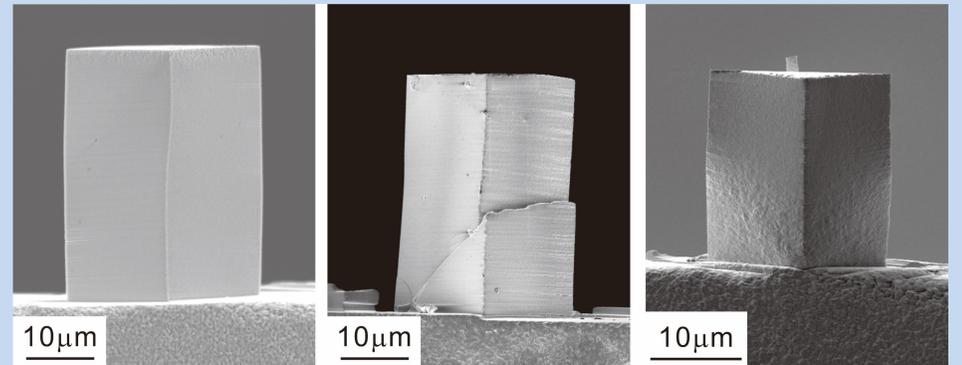
### t-EBSD 300°C annealed



Grain growth and Ni<sub>3</sub>C precipitation observed at 300°C annealing

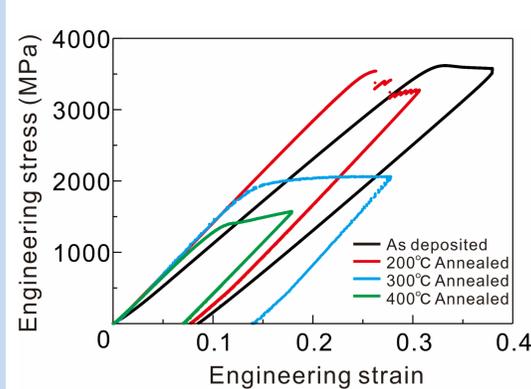
### Mechanical Properties

As deposited      200°C annealed      300°C annealed

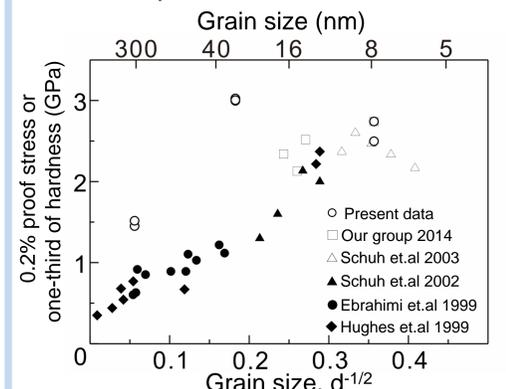


➢ 200°C pillar indicate brittle fracture and others deformed by broad shear banding

### Micro-compression test



### Hall-Petch plot



- Yield strength increased by low temperature annealing.
- Carbon may rearranged on grain boundary which improve boundary strength and form intermetallic on grain boundary.

## CONCLUSIONS

Low temperature annealing of nanocrystalline nickel make material brittle and increase yield strength. Carbon impurity found in nickel film may concentrate on grain boundary by low temperature annealing and produce carbide at grain boundaries which suppress grain growth.